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TITLE : REMOVER COMPOSITION

**ABSTRACT :** PROBLEM TO BE SOLVED: To easily remove a resist hardened or chemically degenerated by high energy treatment by using a remover composition of a specified pH for a resist containing an organic acid and/or its salt, water and a surfactant.

SOLUTION: The remover composition contains an organic acid and/or its salt, water and a surfactant and the pH is <8. The organic acid is, e.g. a carboxylic acid, perchloric acid or periodic acid but a carboxylic acid is preferably used from the viewpoint of the prevention of corrosion of a metallic material. The salt is, e.g. the salt of the organic acid and a basic organic compound such as a primary or secondary amine or a basic inorganic compound such as ammonia or sodium hydroxide. The water is preferably ion exchanged water or pure water having minimized ionic substance and particle contents. The surfactant is, e.g. an anionic or cationic surfactant. The pH of the remover composition is preferably 0.1-7 from the viewpoint of resist removing ability.

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